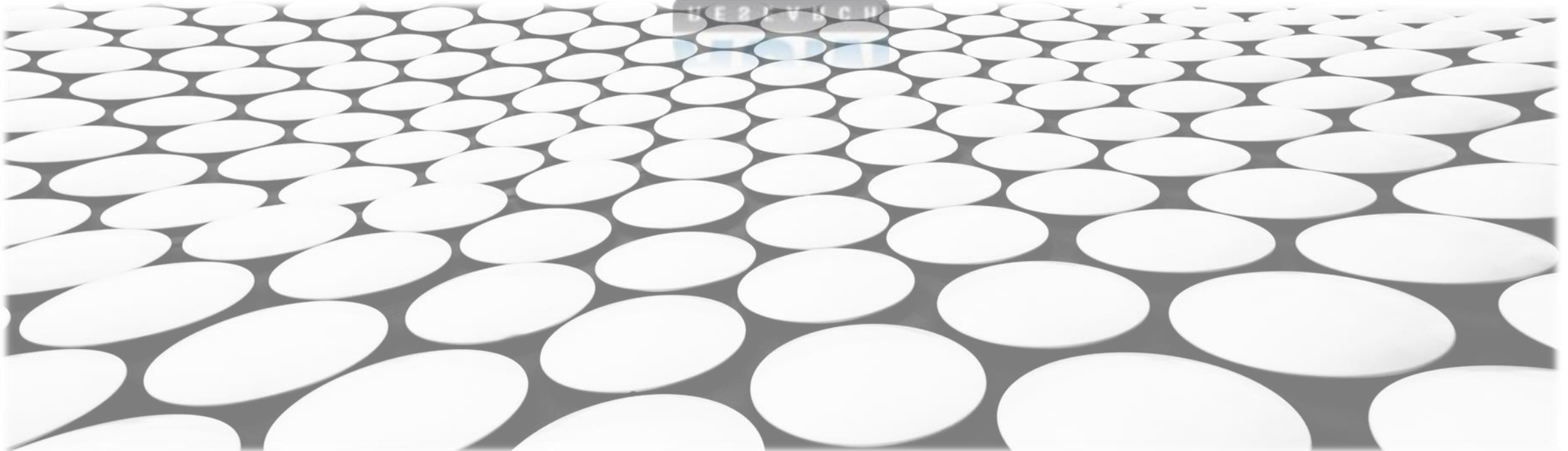




ACM Research, Inc.

May 2024 Investor Presentation





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Market Data. Information presented below concerning ACM Research’s total addressable market presents a forecast based on information provided by Gartner, Inc. in its report “Forecast: Semiconductor Wafer Fab Equipment, Worldwide, 4Q23 Update” (December 2023). You are cautioned not to rely on or give undue weight to this information. The Gartner report represents research opinions or viewpoints that are published, as part of a syndicated subscription service, by Gartner and are not representations of fact. The Gartner report speaks as of its original publication date (and not as of the date of this presentation), and the opinions expressed in the Gartner report are subject to change without notice. While ACM Research is not aware of any misstatements regarding the information provided in the Gartner report, it has not independently verified the accuracy or completeness of that information, which involves numerous assumptions and is subject to risks and uncertainties, as well as change based on various factors, that could cause results to differ materially from the forecast presented. The industry in which ACM Research operates is subject to a high degree of uncertainty and risk due to variety of factors, including those described in ACM Research public filings with the SEC, as described above.

Note Regarding Presentation of Non-GAAP Financial Measures. Information presented below under “Q1 2024 Summary” and “Q1 2024 Financial Results” includes certain “non-GAAP financial measures” as defined in Regulation G under the Securities Exchange Act of 1934, including non-GAAP gross margin, non-GAAP operating income, non-GAAP basic and diluted EPS, and non-GAAP gross profit. These supplemental measures exclude the impact of stock-based compensation and unrealized gain or loss on short term investments, which ACM Research does not believe are indicative of its core operating results. A reconciliation of each non-GAAP financial measure to the most directly comparable GAAP financial measure is included below “Q1 2024 GAAP to Non-GAAP Reconciliation.” ACM Research believes these non-GAAP financial measures are useful to investors in assessing its operating performance. ACM Research uses these financial measures internally to evaluate its operating performance and for planning and forecasting of future periods. Financial analysts may focus on and publish both historical results and future projections based on the non-GAAP financial measures. ACM Research also believes it is in the best interests of investors for ACM Research to provide this non-GAAP information.

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Company References. As used in this presentation, “ACM Shanghai” refers to ACM Research (Shanghai), Inc., “ACM South Korea” refers to Hanguk ACM CO., LTD, and “ACM Research” refers to ACM Research, Inc. and its subsidiaries, including ACM Shanghai and ACM South Korea.

ACM Research at a Glance



- **Multi-product supplier of semiconductor capital equipment** to leading global semiconductor manufacturers
- **Differentiated technology** improves customer production processes with better yields and reduced chemical consumption
- **More than 498 patents** issued in the U.S., China, Japan, Singapore, South Korea and Taiwan as of 12/31/23
- **State-of-the-art production facilities** in Chuansha & Zhangjiang, Shanghai; construction is nearly completed for new R&D and production center in Lingang, Shanghai
- **Headquartered in Fremont, CA** with more than 1,590 employees globally as of 12/31/23

Cleaning

Flagship (SAPS, TEBO, Tahoe, Bevel Etch, SPM)

Self-critical



ECP, Furnace & Other

Ultra ECP ap

Ultra ECP map

Ultra Fn Furnace



NEW Products: Track and PECVD

Track

PECVD



Advanced Packaging & Other

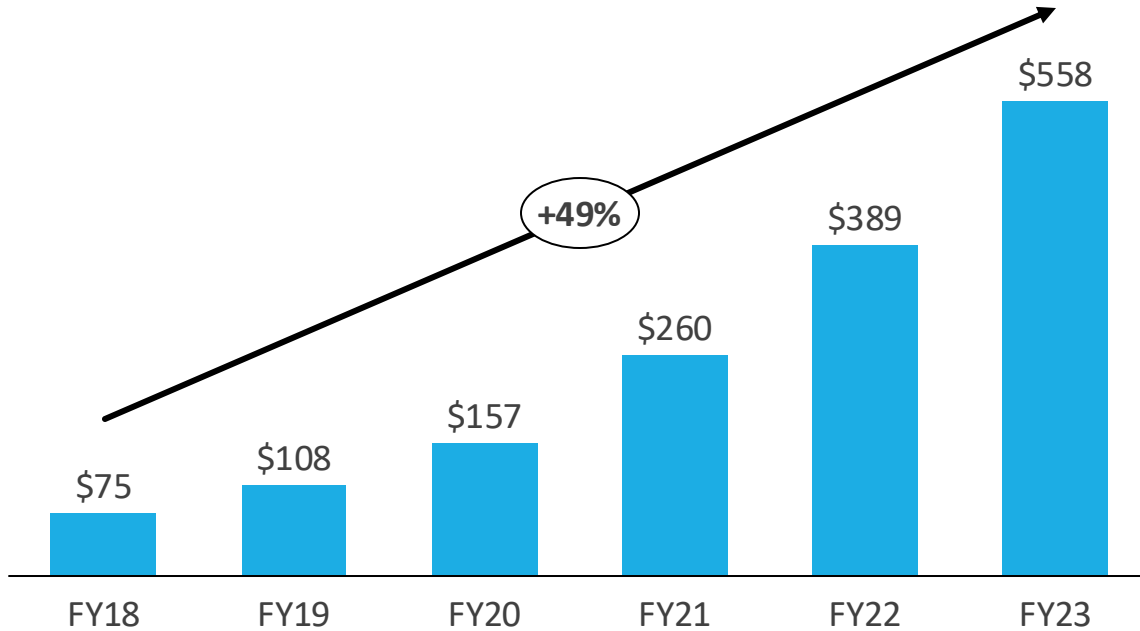
Scrubbers, coaters, developer tools, plating tools, tape frame cleaning, wet stripping, wet etching and stress-free polishing systems, and other parts and services



Financial Highlights

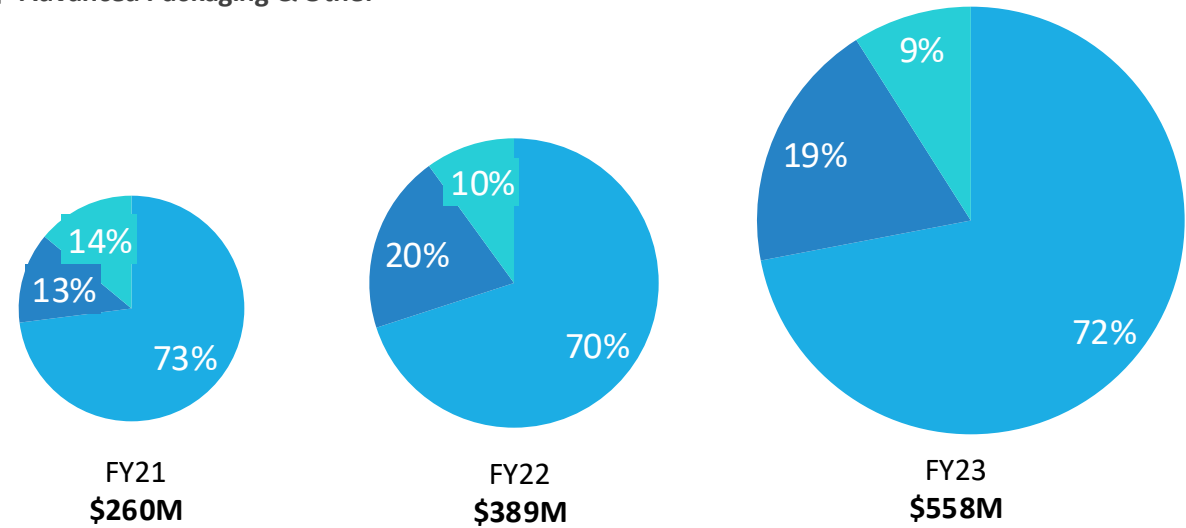


Total Revenue



Product Mix

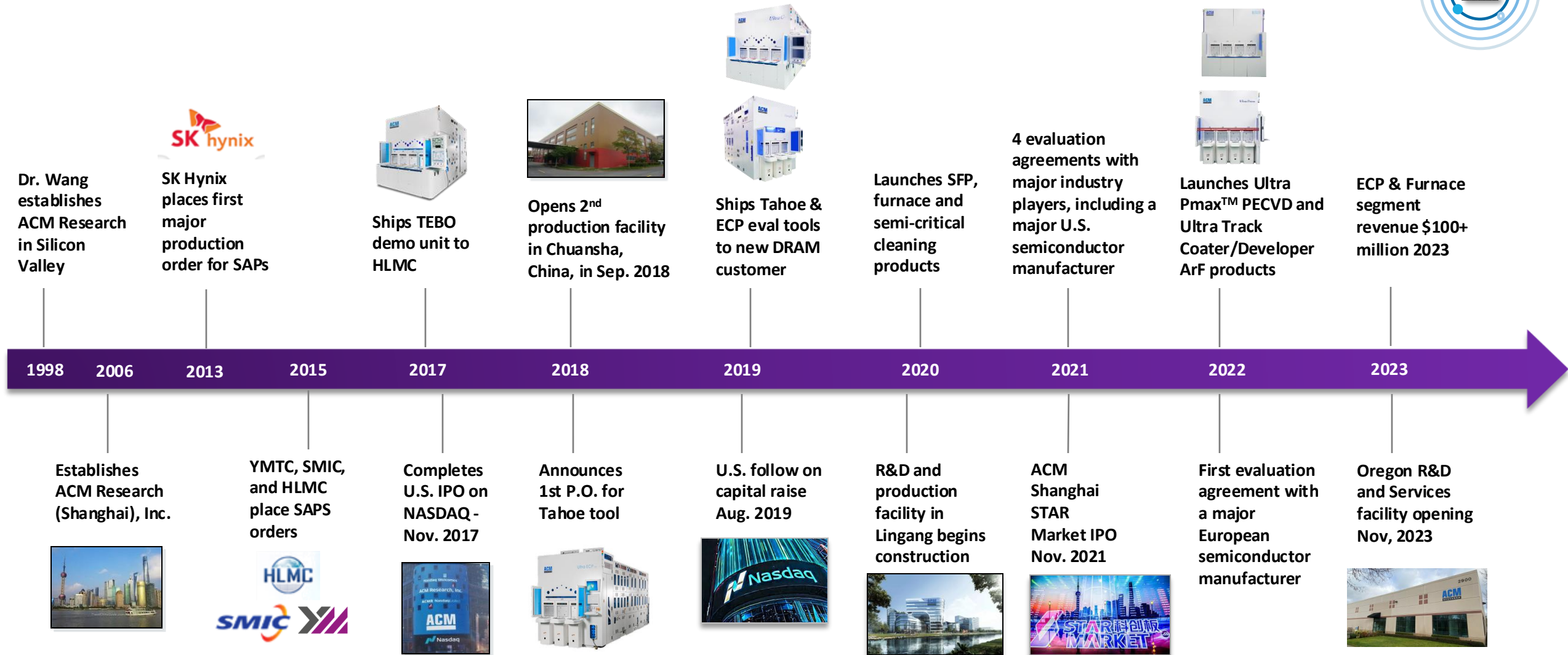
- Cleaning
- ECP, Furnace & Other
- Advanced Packaging & Other



1. Cleaning: Single wafer cleaning, Tahoe and semi-critical cleaning equipment
2. ECP, Furnace & Other: ECP (front-end and packaging), furnace and other technologies
3. Advanced Packaging & Other: Advanced Packaging (excluding ECP), services & spares

ACM Research achieved 49% revenue CAGR over past 5 years and has diversified its product mix into new product categories

History of Innovation and Customer Design Wins



Global Semiconductor Capital Equipment Supplier



ACM Research HQ
Nasdaq: ACMR



Europe Facility
Sales & Services

ACM Shanghai
R&D and Manufacturing Center



Shanghai R&D Center
(Zhangjiang)



Shanghai Asia-Pacific Manufacturing Center
>200,000 ft² (Chuansha)



Planned >1.4 million ft²
(Lingang)

ACM South Korea
Research Institute &
Manufacturing Center

Oregon Facility
Sales, Services & Demo Center



Tier 1 Customer Base



Front-End Customers

Back-End Customers



- ACM 2023 Revenue %: 18%
- Mainland China's largest foundry
- Tier-one customers include Qualcomm, Broadcom and Texas Instruments ⁽¹⁾



- ACM 2023 Revenue %: 15%
- A semiconductor integrated circuit developer in China



- ACM 2023 Revenue %: 13%
- New China-based entrant to DRAM industry



- Largest bumping house in China and leading WLCSP production base
- Subsidiary of OSAT company JGET
- Owns one of the most advanced packaging technology R&D service platforms⁽³⁾
- Global customer base with exposure to the U.S., Western Europe and Asia



- Major new entrant into NAND flash and DRAM industry
- Innovative Xtacking 2.0 unleashes potential of 3D NAND ⁽²⁾



- Leading advanced foundry in China

Tier 2 and 3 China-based IC Manufacturers

- Tier 2 includes Hangzhou Silan and 4 China-based customers
- Ordered a range of semi-critical tools including the scrubber, wet etch, and backside wafer etching tool, auto wet bench, SAPS-II cleaning tool and Cu interconnect ECP map tool.
- Tier 3 includes a handful of companies investing in new capacity in IoT, EV, AI



- Leading OSAT provider – #4 globally⁽⁴⁾ and top 3 in China⁽⁴⁾
- Fastest growing OSAT provider globally with ~30% year-over-year revenue growth in 2022⁽⁴⁾
- Six production facilities serving more than half of the top ten global semiconductor manufacturers⁽⁴⁾

(1) Source: SMIC website. (2) Source: YMTC Press Release. (3) Source: JCAP Company Profile. (4) Source: TFME website.

Innovative Product Introductions Expanding Serviceable Available Market (“SAM”)¹

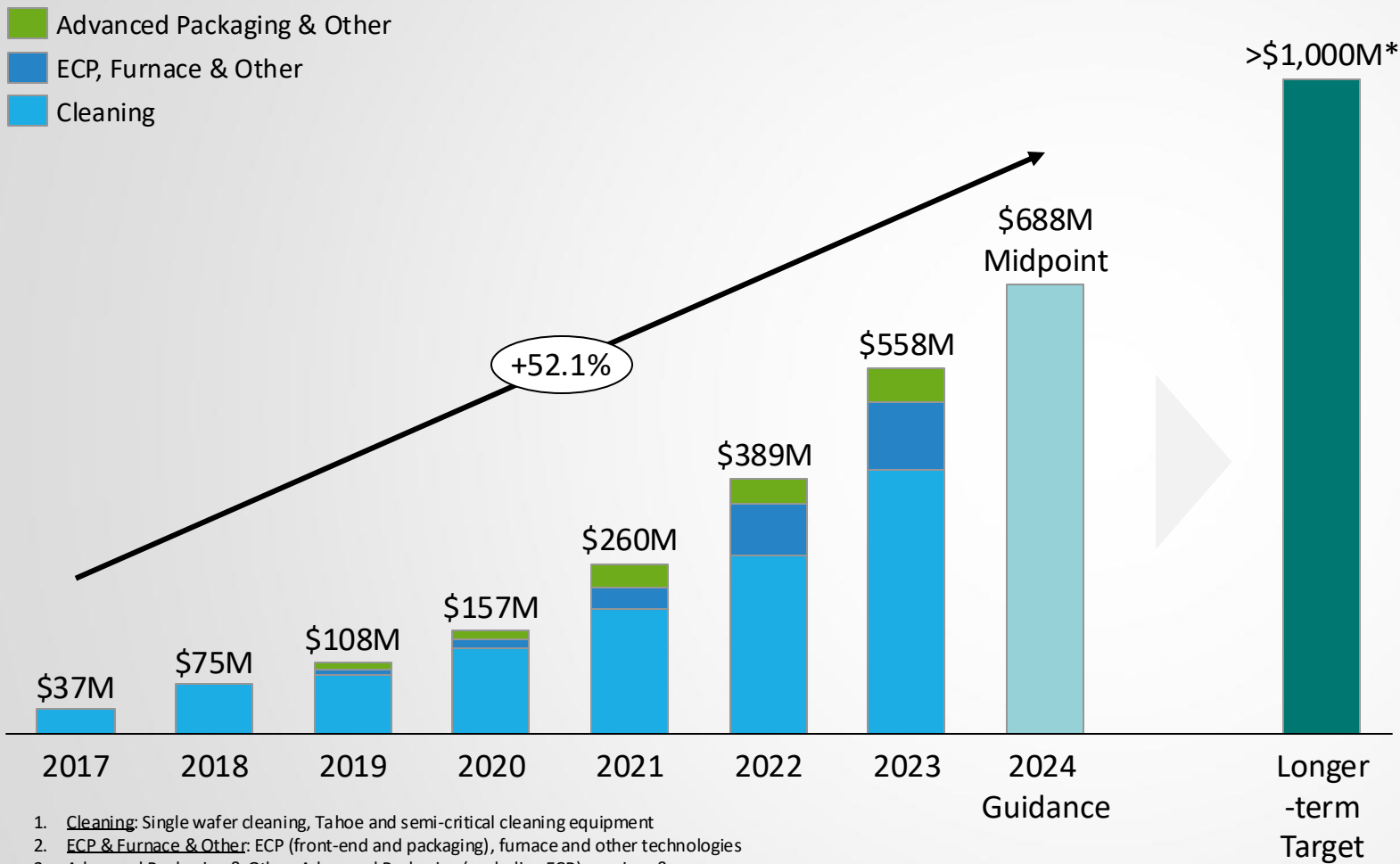


Estimated 2023 SAM of \$16 billion addressed by ACM’s current product portfolio



¹Source: Gartner - “Forecast: Semiconductor Wafer Fab Equipment, Worldwide, 4Q23 Update” (December 2023) and Company Estimates

Longer-Term Target for \$1B+ in Revenue



- Cleaning:** Single wafer cleaning, Tahoe and semi-critical cleaning equipment
- ECP & Furnace & Other:** ECP (front-end and packaging), furnace and other technologies
- Advanced Packaging & Other:** Advanced Packaging (excluding ECP), services & spares

* ACM longer-term internal target, for internal planning purposes only, not a projection or estimate of actual or future revenue

Longer Term Target Composition			
		ACM Research	
Mainland China	SAM ¹	Share	Revenue
Cleaning	\$0.8B	55%	\$0.4B
ECP	\$0.2B	50%	\$0.1B
Furnace	\$0.3B	35%	\$0.1B
PECVD	\$0.7B	15%	\$0.1B
Track	\$0.4B	15%	\$0.1B
Ad. Packaging	n/a	n/m	\$0.2B
	\$2.4B	40%	\$1.0B
RoW			
Cleaning	\$4.4B	-	
ECP	\$0.6B	-	Upside
Furnace	\$1.9B	-	
PECVD	\$3.7B	-	-
Track	\$2.1B	-	-
Ad. Packaging	n/a	-	-
	\$12.6B	-	Upside
ACM China + RoW Revenue			>\$1.0B

¹Source: Gartner - "Forecast: Semiconductor Wafer Fab Equipment, Worldwide, 4Q23 Update" (December 2023) and Company Estimates:

- 2023 Gartner WFE market of \$93B
- ACM Global SAM is ~17% of Global WFE and China is 28% of ACM Global SAM



Growth at Existing Customers

- Continue winning share at existing customers
- Continued China fab expansion, particularly in mature nodes
- Accelerating ECP and furnace product cycles

International Expansion

- SAPS cleaning tool qualified for revenue by a large US manufacturer Q4'2023
- Delivered SAPS evaluation tool to major Europe-based global semiconductor manufacturer in Q3'2023
- Expanding sales & services teams in U.S., Europe, Korea and SE Asia
- R&D and Services facility in Hillsboro, Oregon



New Capacity

- Lingang facility on track for initial production for 2024 with target for longer term annual revenue production capacity of \$1.5 billion+
- Purchased new headquarters in Zhangjiang Shanghai, Silicon Valley of China
- Korea R&D and production facility to support international expansion



New Products

- Broad product portfolio covering 90%+ of cleaning process steps including semi-critical, bevel etch, high-temp SPM, and super critical dry CO₂.
- Plating for front and back end, furnace and semi-critical tools
- Added Track & PECVD product categories at end of 2022 that doubled ACM SAM to \$16 billion





Q1 2024 Financial Results

- \$152.2 million revenue (up 105.0% y/y); total shipments of \$245 million (up 175% y/y)
- 52.0% GAAP gross margin (versus 53.8% in Q1 2023)
- 52.5% non-GAAP gross margin (versus 54.0% in Q1 2023)
- \$25.2 million GAAP operating income (16.6% of revenue)
- \$39.8 million non-GAAP operating income (26.2% of revenue)
- \$0.26 diluted GAAP earnings per share (versus \$0.11 in Q1 2023)
- \$0.52 diluted non-GAAP earnings per share (versus \$0.15 in Q1 2023)

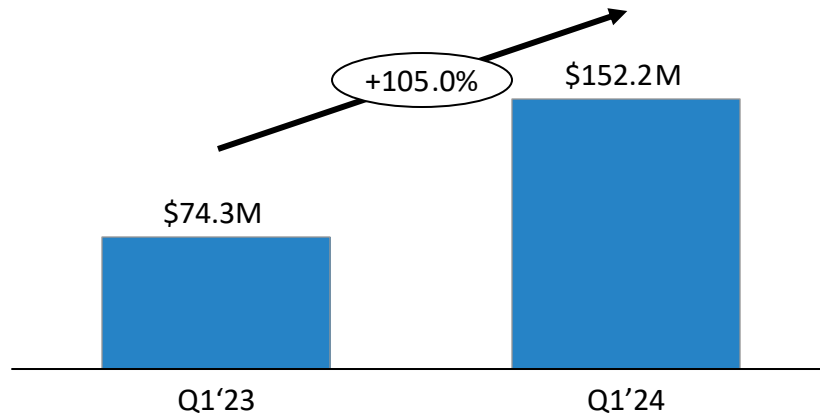
Key Operational Updates

- SPM (Sulfuric-Peroxide Mix) product ramp commencing with Tahoe and single-wafer low and high-temperature tools
- Delivered ULTRA C v Vacuum Cleaning tool to a major customer
- Expanded advanced packaging portfolio with introduction of Frame Wafer Cleaning tool
- Appointed David Kim as CEO of ACM Research Korea CO., LTD
- Lingang production and R&D Center nearly complete; initial production expected to begin later this year.
- Expanding operations in Oregon

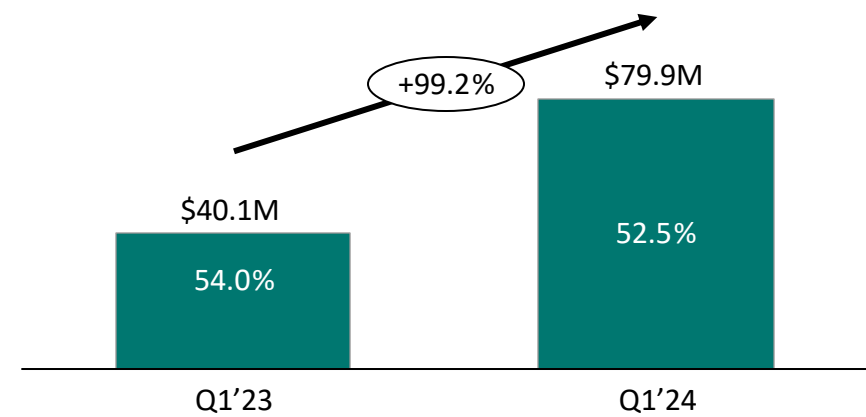
Q1 2024 Financial Results



Revenue

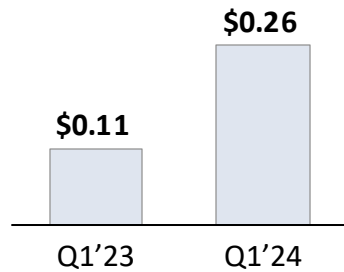


Non-GAAP Gross Profit

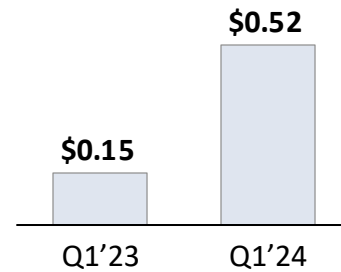


EPS

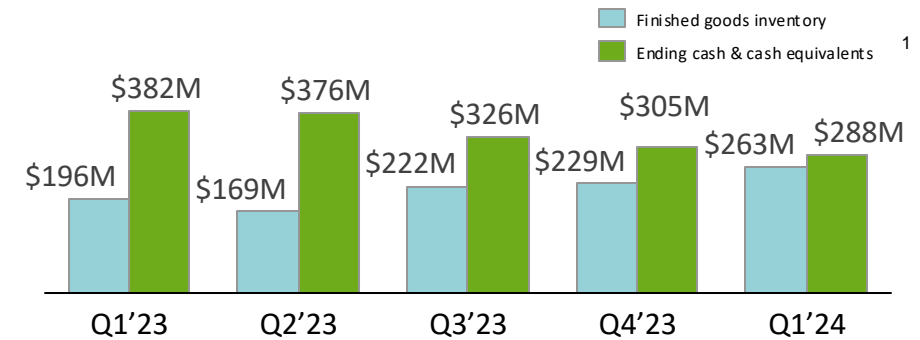
GAAP



Non-GAAP



Balance Sheet



¹ Including interest bearing time deposits.

See slide 19 for reconciliation between GAAP and Non-GAAP Gross Profit and EPS



Revenue by Product: Q1'24 vs Q1'23

Cleaning

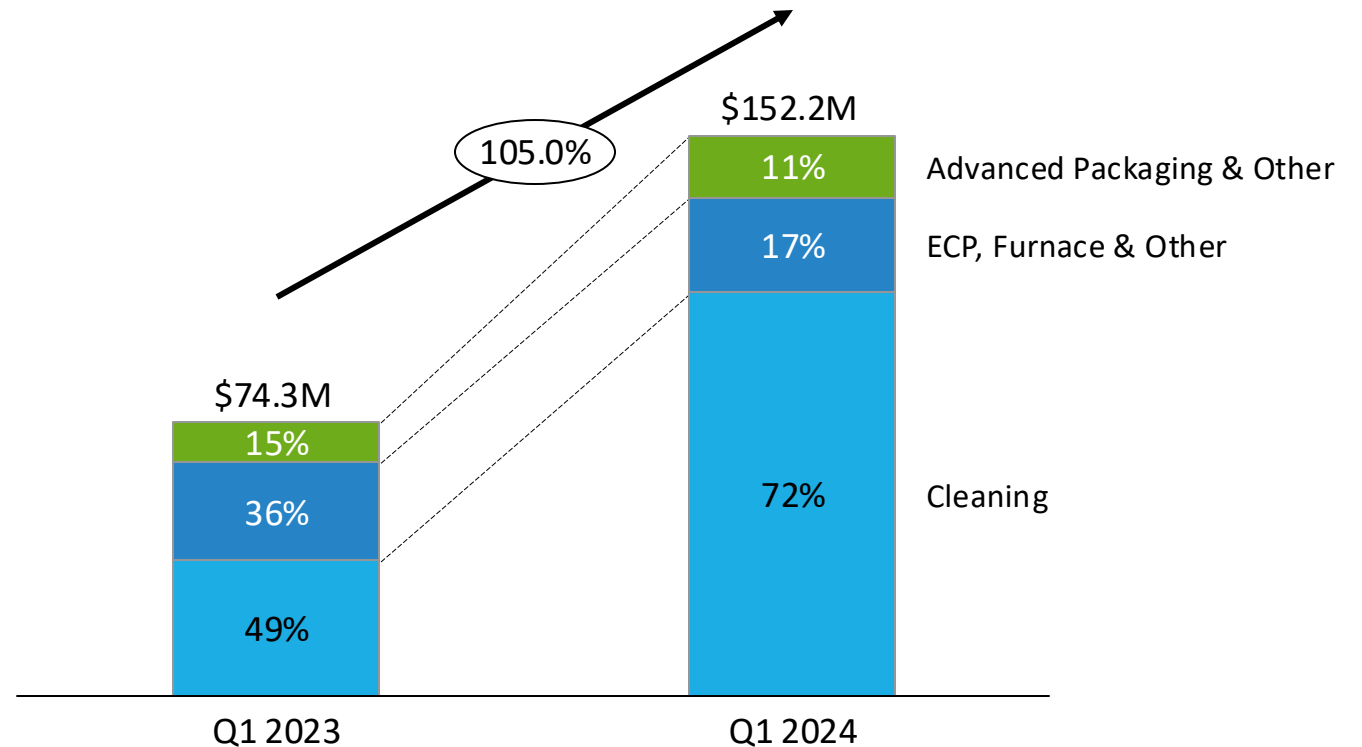
- \$109.5M revenue (up 199% y/y)
- Revenue mix 72% vs. 49%

ECP, Furnace & Other

- \$25.8M revenue (down 3% y/y)
- Revenue mix 17% vs. 36%

Advanced Packaging & Other

- \$16.9M revenue (up 53% y/y)
- Revenue mix 11% vs. 15%



1. Cleaning: Single wafer cleaning, Tahoe and semi-critical cleaning equipment
2. ECP, Furnace & Other: ECP (front-end and packaging), furnace and other technologies
3. Advanced Packaging & Other: Advanced Packaging (excluding ECP), services & spares

Wafer Cleaning



Flagship Cleaning Tools

SAPS



Megasonic Cleaning for Flat and Patterned Wafer Surfaces

- High efficiency with enhanced process flexibility
- Uniform and consistent results
- Customizable specifications

TEBO



Bubble Oscillation Cleaning for Patterned Wafers at Advanced Process Nodes

- Highly effective, damage-free solution for small and fragile features
- Multi-parameter bubble cavitation control

Ultra – C Tahoe



Hybrid Wafer Cleaning With Significant Cost & Environmental Benefits

- Environmentally friendly – uses 10% of the sulfuric acid used than conventional tools
- High cleaning performance at low cost

Bevel Etch



Bevel Etching process for 3D NAND, DRAM and advanced logic processes

- Accurate and efficient wafer center alignment for precise bevel etch
- Variable wafer bevel etch/cut accuracy of 1-7mm and good uniformity

Single Wafer High Temp SPM



Single High Temp SPM Cleaning for metal removal and PR Strip at advance node

- Photoresist stripping after high-dose energy implant, wet stripping without using a dry ash process, and special metal film removal processes at advance node

Semi Critical Cleaning Tools

Auto Bench



Batch Wafer Cleaning for a full range of wet technologies across multiple nodes

- ULD advance drying technology addresses challenges in high-aspect-ratio structures
- MCR module delivers high cleaning performance and eliminates cross-contamination

Backside



Backside Clean Tool for wafer device side none contact process

- Good particle performance and etch uniformity control
- High throughput above 300 wph

Scrubber



Scrubber Cleaning for efficient front- and backside wet-cleaning applications

- High throughput, small footprint and low cost
- Small particle removal

Advance Processes

Supercritical CO2 Dry



Supercritical CO2 Dry for advance DRAM processes

- Damage free drying process for high-aspect-ratio structures including Isolation and Storage node

High Temp IPA Dry (UTD)



High Temp IPA Drying for advance Logic processes

- Damage free drying process for small structures and high-aspect-ratio structures
- Associate with customizable Cleaning method for good cleaning performance.

Electroplating



Model	Ultra ECP map	Ultra ECP 3D	Ultra ECP ap	Ultra ECP ap (Cu-Ni-SnAg-Au)	Ultra ECP GIII
Application	Dual-damascene plating (90nm-28nm)	3D/2.5D high aspect ratio TSV	Pillar bump, Solder bump, RDL, Conformal TSV	High-density Fan Out Fine Pitch RDL	RF product 150mm wafer-level packaging
Module	16 chambers	10/12 chambers	24/28 chambers	28 chambers	8/9 chambers
	Cu Post-cleaning Annealing	Cu Post-cleaning Pre-wetting	Cu+Ni+SnAg Pre-wetting Post-cleaning	Cu/Ni/SnAg/Au Pre-wetting Post-cleaning Cleaning after Au plating	Cu+Sn/Ag+Ni Au Pre-wetting Post-cleaning
Special Features	Impulse local plating	Impulse local plating	Second anode technology	Second anode technology Impulse Au plating	Second anode technology

Vertical Furnace



Furnace Tube Classification	Film Type	Process	Temperature Range	Existing ACM Product	In Development
Normal Pressure Chemical Vapor Deposition Furnace	Oxidation	Wet oxygen/dry oxygen/nitrogen annealing	700~1200°C	★	
	Annealing				
	Back-end thermal treatment	Copper process thermal treatment	100~450°C		
Coating and curing					
Low Pressure Chemical Vapor Deposition Furnace	Alloy	Hydrogen/nitrogen thermal treatment	100~450°C	★	
	Silicon deposition	Poly-crystal silicon doping	500~620°C	★	
		Advanced poly-crystal deposition			☆
		No poly-crystal silicon doping		★	
	Silicon oxide	High-temperature silicon oxide	650~800°C	★	
Silicon nitride	Silicon nitride deposition	★			
Atomic Layer Deposition Furnace	Silicon oxide	Silicon oxide deposition	500~650°C	★	
	Silicon nitride	Silicon nitride deposition			

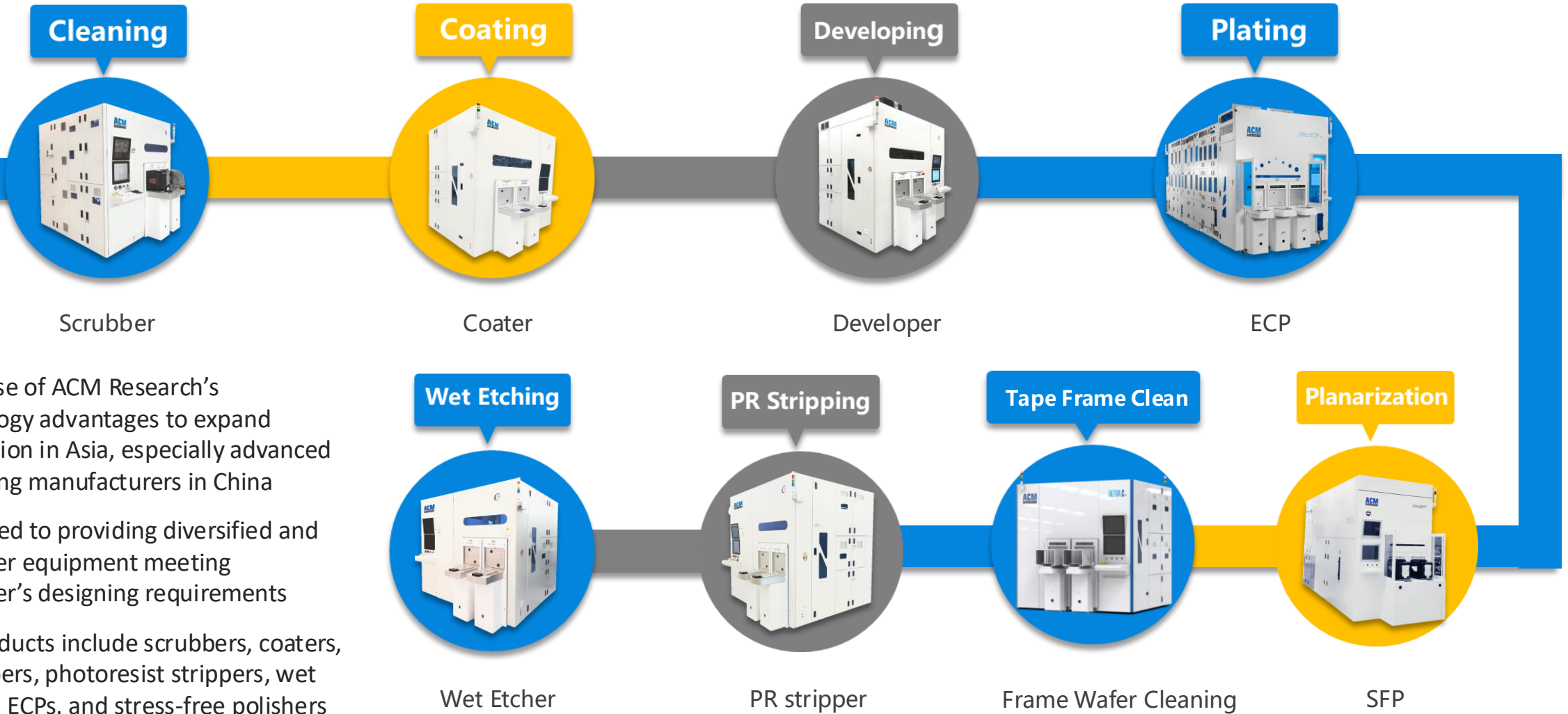


W*L*H= 1.10m*3.70m*4.05m

Advanced Packaging





Comprehensive solution for wafer-level advanced packaging wet process



- Make use of ACM Research's technology advantages to expand application in Asia, especially advanced packaging manufacturers in China
- Dedicated to providing diversified and customer equipment meeting customer's designing requirements
- The products include scrubbers, coaters, developers, photoresist strippers, wet etchers, ECPs, and stress-free polishers



Model	Model	Technical Features	Offline/Inline	Chamber Temperature	Bake Range	Development Phase
 Ultra Lith™ Track Coater/Developer --- ---	ArF Model	<ul style="list-style-type: none"> ✓ Support 300mm wafers ✓ Four 12-inch load ports ✓ 8 coating chambers ✓ 8 developing chambers 	Inline	23°C ±0.1°C	50~250°C	Industry Evaluation
	KrF Model			---	---	In Development
	I-line Model			---	---	In Development

Model	Film Category	Film Type	RF Frequency	RF Control	Heater/CH	Development Phase
 Ultra Pmax™ PECVD	SiH4 Base	SiO ₂ ; Si ₃ N ₄ ; SiON	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	Industry Evaluation
	TEOS Base	TEOS Layer	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	
	Chemical Base	SiCN/APF Layer	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	

Q1 2024 GAAP to Non-GAAP Reconciliation



	Three Months Ended March 31,							
	2024				2023			
	Actual (GAAP)	SBC	Other non- operating adjustments	Adjusted (Non-GAAP)	Actual (GAAP)	SBC	Other non- operating adjustments	Adjusted (Non-GAAP)
	<i>(In thousands)</i>							
Revenue	\$ 152,191	\$ -	\$ -	\$ 152,191	\$ 74,256	\$ -	\$ -	\$ 74,256
Cost of revenue	(73,070)	(781)	-	(72,289)	(34,270)	(125)	-	(34,145)
Gross profit	79,121	(781)	-	79,902	39,986	(125)	-	40,111
<i>Gross margin</i>	<i>52.0%</i>	<i>0.5%</i>	-	<i>52.5%</i>	<i>53.8%</i>	<i>0.2%</i>	-	<i>54.0%</i>
Operating expenses:								
Sales and marketing	(14,173)	(3,027)	-	(11,146)	(9,337)	(431)	-	(8,906)
Research and development	(23,918)	(4,503)	-	(19,415)	(14,029)	(701)	-	(13,328)
General and administrative	(15,798)	(6,258)	-	(9,540)	(7,758)	(811)	-	(6,947)
Total operating expenses	¹ (53,889)	(13,788)	-	(40,101)	(31,124)	(1,943)	-	(29,181)
Income (loss) from operations	\$ 25,232	\$ (14,569)	\$ -	\$ 39,801	\$ 8,862	\$ (2,068)	\$ -	\$ 10,930
Unrealized loss on short-term investments	(2,595)	-	(2,595)	-	(654)	-	(654)	-
Net income (loss) attributable to ACM Research, Inc.	\$ 17,433	\$ (14,569)	\$ (2,595)	\$ 34,597	\$ 7,145	\$ (2,068)	\$ (654)	\$ 9,867
Basic EPS	\$ 0.28			\$ 0.56	\$ 0.12			\$ 0.17
Diluted EPS	\$ 0.26			\$ 0.52	\$ 0.11			\$ 0.15